

FORM PTO-1449	Docket No.: 2004P51130US/1331.128.101	Serial No.: 10/816, 503
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	Applicant: Hong-Jyh Li	
	Filing Date: Herewith	Group Art: 2887

U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate
98	AA 6,660,660	12/09/2003	Haukka et al.			
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
	AL					

FOREIGN PATENT DOCUMENTS

	Document No.	Date	Country	Class	Sub Class	Translated Yes No
AM						Yes
AN						Yes

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

9	AP	Yankov, Rossen A. and Mändl, Stephan, "Plasma Immersion Ion Implantation for Silicon Processing", Ann. Phys. (Leipzig) 10 4, pp. 279-298, (2001).
9	AQ	Ensinger, W., "Semiconductor Processing by Plasma Immersion Ion Implantation", Materials Science and Engineering, pp. 258-268, (1998).

EXAMINER: *Shelly J. Hunt* **DATE CONSIDERED:** 9-15-05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.